

Remarks/Argument

Office Action Summary

In the Office Action dated January 4, 2007, the Examiner rejected claims 6-8 and 10-15 under 35 U.S.C. § 103(a) as being unpatentable over Applicant admitted prior art ("APA") in view of Lee (U.S. Patent No. 6,214,751) ("Lee1") and Lee et al. (U.S. Patent No. 6,819,969) ("Lee2.")

Claim Summary

Applicant wishes to thank the Examiner for meeting with the Applicant's representative during an interview on February 19, 2007. The remarks presented below are consistent with the topics discussed and agreements reached during the interview. By this Reply, Applicant has amended claims 6, 10, and 12, and has cancelled claim 15. Specifically, Applicant has amended claim 6 in a manner agreed upon by the Examiner during the interview of February 19, 2007. Therefore, Applicant believes that claim 6, as amended, is in a condition of allowance. Claims 6-8 and 10-14 remain pending in this Application.

35 U.S.C § 103 Rejection – Claims 6-8 and 10-15.

Applicant respectfully traverses the rejection of claims 6-8 and 10-15 under 35 U.S.C. § 103(a) as being unpatentable over APA in view of Lee1 and Lee2. No *prima facie* case of obviousness has been established for at least the reason that the combination of APA, Lee1 and Lee2 fails to disclose each and every claim element. For example, amended claim 6 now includes a combination of claim recitations including, *inter alia*, "cleaning the inside of the chamber . . . using a cleaning gas which is different than the process gas . . . wherein the substrates are processed at a given deposition temperature within the chamber, and wherein the

process gas is supplied into the chamber, without exciting the process gas with RF power, for a sufficient time so as to reduce the temperature prevailing inside the chamber to the deposition temperature.” The combination of APA, Lee1, and Lee2 fails to disclose at least these claim elements.

In the Office Action, the Examiner maintained that APA discloses “supplying a gas into the chamber to reduce the temperature inside the chamber.” See Office Action page 2, paragraph 2. Applicant respectfully submits that the Examiner has misinterpreted APA. Instead, APA discloses that the temperature inside the chamber is actually **increased** during the cleaning. See, for example, Specification page 5, paragraph [0050]. Nevertheless, the Examiner admitted that APA does not disclose supplying the process gas without exciting the gas with RF power. See Office Action page 3.

However, the Examiner relied on Lee1 and Lee2 for their apparent disclosure of supplying a process gas without exciting the process gas with RF power. See Office Action pages 3 and 4. . Applicant respectfully submits that no portion of Lee1 and Lee2 discloses “cleaning the inside of the chamber . . . using a **cleaning gas which is different than the process gas**” and “wherein the substrates are processed at a given deposition temperature within the chamber, and wherein the process gas is supplied into the chamber, without exciting the process gas with RF power, **for a sufficient time so as to reduce the temperature prevailing inside the chamber to the deposition temperature,**” as featured in claim 6. (Emphasis added.)

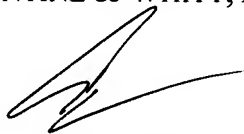
Therefore, for at least the reason that the combination of APA, Lee1, and Lee2 fails to disclose each and every claim element, the Section 103 Rejection of claim 6 should be withdrawn. Claims 7, 8 and 10-14 ultimately depend from claim 6 and, therefore, are allowable for at least the reasons discussed above and in view of their additional recitations of novelty.

Conclusion

No other issues remaining, reconsideration and favorable action upon the claims 6-8 and 10-14 now pending in the application are requested.

Respectfully submitted,

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